## IN THE CLAIMS

Claims 1 and 4-6 are pending in this application. Please amend claim 1 as follows:

1. (Currently Amended) A display device forming a display region where a plurality of films including an insulation film, a semiconductor film and a conductive film are patterned in a given pattern and stacked on a substrate, wherein

at a point of time that at least one correction portion out of a correction portion which separates a short-circuit defect, a correction portion which connects an opening defect, a correction portion which removes a standard deviation defect, and a correction portion which separates a standard deviation defect of the pattern is corrected, at least one upper-layer film is formed above a film to be corrected at the correction portion and overlaps the correction portion, the correction is applied to the film to be corrected while the upper-layer film remains at a region which overlaps the correction portion, and

the correction of the correction portion is performed by the irradiation of a laser beam through the at least one upper-layer film from a side of the at least one upper-layer film opposite the substrate and not through a substrate.

## 2-3. (Canceled).

- 4. (Previously Presented) A display device according to claim 1, wherein the laser beams are irradiated to the same portion by dividing the laser beams plural times.
- 5. (Original) A display device according to claim 1, wherein the upper-layer film above the film to be corrected includes at least either one of an insulation film and a transparent conductive film.
- 6. (Original) A display device according to claim 1, wherein a display of the display region is performed normally due to the correction of the correcting portions.
- 7. (Withdrawn) A manufacturing method of a display device comprising:

a film forming step in which a plurality of films including an insulation film, a semiconductor film and a conductive film are stacked onto a substrate; and

a defect portion correcting step in which at least one correction out of a short-circuit defect portion separation correction which separates a short-circuit defect, an open defect portion connection correction which performs a connection of an open defect, a standard deviation defect portion removal correction which performs a removal of a standard deviation defect, and a standard deviation defect portion separation correction which performs a separation of a standard deviation defect portion generated in the formed film is performed, wherein

at a point of correction time of the defect portion correction step, at least one upper-layer film is present above a film to be corrected at the correction portion and the correction is applied to the film to be corrected while leaving the upper-layer film as it is.

- 8. (Withdrawn) A manufacturing method of a display device according to claim 7, wherein the correction is performed by irradiating laser beams.
- 9. (Withdrawn) A manufacturing method of a display device according to claim 8, wherein the laser beams are irradiated to the substrate from a side opposite to the substrate.
- 10. (Withdrawn) A manufacturing method of a display device according to claim 8, wherein the laser beams are irradiated to the same portion by dividing the laser beams plural times.
- 11. (Withdrawn) A manufacturing method of a display device according to claim 10, wherein the laser beams are irradiated to the same portion by dividing the laser beams at least 10 times.
- 12. (Withdrawn) A manufacturing method of a display device according to claim 10, wherein an irradiation interval of the laser beams is equal to or more than 0.3 seconds.
- 13. (Withdrawn) A manufacturing method of a display device according to claim 8, wherein a wavelength of the laser beams is set to a wavelength which allows the laser beams to be more easily absorbed in the film to be corrected than the upper-layer film.

- 14. (Withdrawn) A manufacturing method of a display device according to claim 8, wherein when the film to be corrected is an amorphous silicon semiconductor film, a wavelength of the laser beams is set to 250 nm to 360 nm.
- 15. (Withdrawn) A manufacturing method of a display device according to claim 8, wherein an output of the laser beams is set to 0.02W/cm<sup>2</sup> or less.
- 16. (Withdrawn) A manufacturing method of a display device according to claim 15, wherein the laser beams to be irradiated to the same portion are irradiated by dividing the laser beams 10 or more times.
- 17. (Withdrawn) A manufacturing method of a display device according to claim 7, wherein the upper-layer film includes at least either one of an insulation film and a transparent conductive film.
- 18. (Withdrawn) A manufacturing method of a display device according to claim 7, wherein the semiconductor film is an amorphous semiconductor film and the amorphous semiconductor film is subjected to the separation correction or the removal correction.
- 19. (Withdrawn) A manufacturing method of a display device according to claim 7, wherein an activated layer of a thin film transistor which has a source electrode and a drain electrode is constituted by the semiconductor film, the semiconductor film includes an intrinsic semiconductor film and a contact film formed over the intrinsic semiconductor film, wherein the separation correction of a defect which short-circuits the source electrode and the drain electrode through the contact film is performed by removing the contact film present between the source electrode and the drain electrode together with a portion of the intrinsic semiconductor film.
- 20. (Withdrawn) A manufacturing method of a display device according to claim 7, wherein the conductive film is at least one of a scanning signal line, a video signal line and a pixel electrode, and the separation correction is at least one of corrections

of a short-circuit defect between the scanning signal lines, a short-circuit defect between the video signal lines and a short-circuit defect between the pixel electrodes.

- 21. (Withdrawn) A manufacturing method of a display device according to claim 20, wherein the pixel electrode is a transparent conductive film.
- 22. (Withdrawn) A manufacturing method of a display device according to claim 7, wherein a normal display is performed by the correction.